

Art Unit: 1774

CLMPTO

EVH

Claims 1-35 are cancelled.

1 36. A nanostructure comprising:
2 (a) a substrate having a surface;
3 (b) a patterned imaging layer of self-assembled monolayer
4 on the surface of the substrate having a pattern therein of separated
5 regions with a spacing of the regions of 100 nm or less;

6 (c) a block copolymer layer on the imaging layer, the
7 block copolymer layer having separated regions of one component of the
8 copolymer that coincide with the separated regions on the imaging layer.

1 37. The microstructure of Claim 36 wherein the thickness
2 of the copolymer layer is 100 nm or less.

1 38. The microstructure of Claim 36 wherein the substrate
2 is formed of single crystal silicon.

1 39. The microstructure of Claim 36 wherein the imaging
2 layer is an alkylsiloxane self-assembled monolayer.

1 40. The microstructure of Claim 36 wherein the imaging
2 layer is an octadecyltrichlorosilane self-assembled monolayer.

1 41. The microstructure of Claim 36 wherein the copolymer
2 layer is a copolymer of polystyrene and poly(methyl methacrylate).